8th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials /
9th International Conference on Plasma-Nano Technology & Science

ISPlasma2016/IC-PLANTS2016

March 6-10, 2016
Nagoya University, Nagoya, Japan

Organizing Committee

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ISPlasma2016 / IC-PLANTS2016 Organizing Committee
Co-Sponsored by：The Japanese Association for Crystal Growth The Japan Society of Plasma Science and Nuclear Fusion Research

http://www.isplasma.jp/

※The photograph is an image.

Registration

Advanced Online Registration is required.

		General	Student
Registration Fee：	Early Registration（Until Feb 20, 2016）	JPY 45,000	JPY 15,000
	On-site Registration	JPY 50,000	JPY 20,000
Tutorial Fee：	Participant in Main Symposium	JPY 1,000	JPY 1,000
	Tutorial Registration Only	JPY 10,000	JPY 5,000
Banquet Fee（on March 8, 2016）		JPY 6,000	JPY 3,000

＊Refunds cannot be made at any reason.

Access

Centrair
(Central Japan International Airport)

To Downtown Nagoya

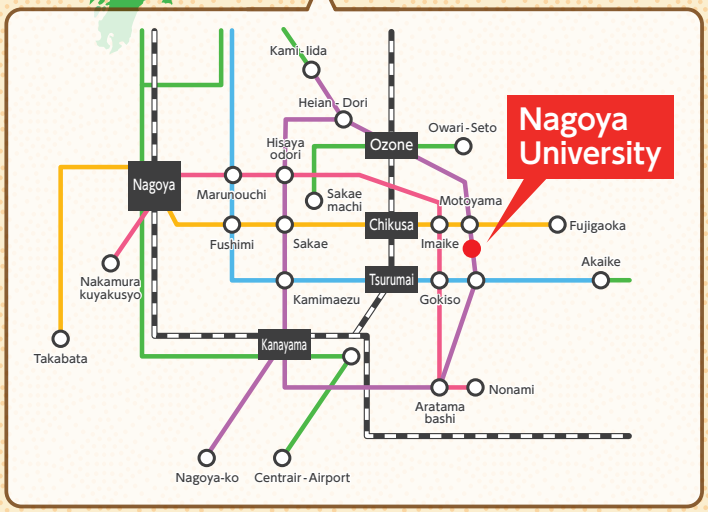
●By Train
・25 min by "Meitetsu Express" to Kanayama St.
・30 min by "Meitetsu Express" to Nagoya St.

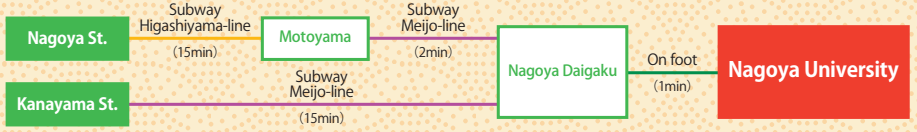
NARITA AIRPORT
To Nagoya Station

●By Train
1 hr. by "Narita Express" to Tokyo St.
→1 hr. 40 min by Shinkansen from Tokyo St.

●By Air
1 hr. 10 min to Centrair
→30 min by "Meitetsu Express" from Centrair

＊Conference venue is approx. 500km away from Fukushima.





Contact

Secretariat：Inter Group Corp
E-mail：isplasma2016@intergroup.co.jp Website：http://www.isplasma.jp/

ISPlasma/IC-PLANTS is a specialized international symposium that brings together about 1,000 world-leading scientists and engineers in Nagoya, Japan to discuss latest researches in the fields of advanced plasma science, its applications for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. In this symposium biosensing technologies will be also highlighted, because of their increasing importance in healthcare, agri-food and environmental areas. We hope that this symposium will provide an ideal venue for the exchange of new ideas and information, and also support the initiation or further development of international collaborations among those who work in these multidisciplinary fields.

Related Fields

Plasma Science & Technologies

- Plasma Source
- Modeling & Simulation
- Thin Film Deposition Process
- Flexible Electronics
- Plasma Agriculture
- Advanced Plasma Diagnostics
- Plasma in Liquid
- Etching Process
- Plasma Biology & Medicine
- Plasma for Nano & Green Technologies

Nitride Semiconductors

- Crystal Growth of GaN & Related Materials
- Characterization
- Device Processing
- Electron & Power Devices
- MBE Growth & Nitrogen Source
- Optical & Optoelectronic Devices

Nanomaterials

- Nanodots & Nanoparticles
- 2D Nanomaterials
- Composites & Functionally Grade Materials
- Applications for Energy, Environment, Nanomedicine & Sensing
- Nanotubes, Nanowires & Nanorods
- Porous Materials & Membranes
- Surface Modification & Functionalization

Biosensing

- Detection Technologies
- Electrochemical Devices
- Biomarkers & Biosensor Surfaces
- Biomaterials
- Detection Technologies
- Biosensors
- Fabrication Technologies
- Biodevices, μTAS, Lab on a Chip

Abstract Submission

Online abstract submission (one-page English) is available from **http://www.isplasma.jp/**

Submission Deadline：~~Monday, Oct 5, 2015 JST~~
Friday, Oct 23, 2015 JST

Special Issue

Selected papers will be published in a special issue of a scientific journal.

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors Nanomaterials and Biosensing will be held on Sun, March 6, 13:00

PROGRAM

Plenary Speaker

Akira Fujishima (Tokyo University of Science, JAPAN)

Keynote / Invited Speakers

Keynote Speaker

S. Hwang (Samsung, KOREA)

Invited Speakers

M. Bockowski (Unipress, POLAND)
Y. Darma (Institut Teknologi Bandung, INDONESIA)
D. Go (University of Notre Dame, USA)
T. Hashizume (Hokkaido University, JAPAN)
A. Koshio (Mie University, JAPAN)
D. Li (Changchun Institute of Optics, CHINA)
S. Rajan (The Ohio State University, USA)
C. Skierbiszewski (Unipress, POLAND)
K. Ueno (Saitama University, JAPAN)
J. Xu (Nanjing University, CHINA)
P. R. Cabarrocas (Ecole Polytechnique, FRANCE)
B. Daudin (CEA-Grenoble, FRANCE)
S. Hara (Hokkaido University, JAPAN)
H. Hirayama (RIKEN, JAPAN)
N. E. Lee (Sungkyunkwan University, KOREA)
A. Matsumoto (Tokyo Medical and Dental University, JAPAN)
L. Schowalter (Crystal IS, Inc. , USA)
A. Subramaniam (Nanyang Technological University, SINGAPORE)
M. J. Wang (National Taiwan University of Science and Technology, TAIWAN)
T. Yanagida (Kyushu University, JAPAN)

Tutorial Speakers

T. Ichiki (The University of Tokyo, JAPAN)
K. Shiraishi (Nagoya University, JAPAN)
K. Matsumoto (Taiyo Nippon Sanso Corp. , JAPAN)
C. Wetzel (Rensselaer Polytechnic Institute, USA)